

Notice of Allowability	Application No.	Applicant(s)	
	10/606,693	JANG ET AL.	
	Examiner Brook Kebede	Art Unit 2823	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. This communication is responsive to 08 April 2005.
2. The allowed claim(s) is/are 1-6.
3. The drawings filed on 08 April 2005 are accepted by the Examiner.
4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some* c) None of the:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.

THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) hereto or 2) to Paper No./Mail Date _____.
 - (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. Notice of References Cited (PTO-892)
2. Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. Information Disclosure Statements (PTO-1449 or PTO/SB/08),
Paper No./Mail Date _____
4. Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. Notice of Informal Patent Application (PTO-152)
6. Interview Summary (PTO-413),
Paper No./Mail Date _____.
7. Examiner's Amendment/Comment
8. Examiner's Statement of Reasons for Allowance
9. Other _____.

Brook Kebede
BROOK KEBEDE
PATENT EXAMINER

DETAILED ACTION

1. The formal drawings were received on April 8, 2005. These drawings are acceptable.

EXAMINER'S AMENDMENT

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Mark C. Zimmerman on June 24, 2005.

3. The application has been amended as follows:

In the Claims:

Change claim 1 to --A method for making shallow trench type pixel for complimentary metal oxide semiconductor (CMOS) image sensor, comprising: forming a CMOS image sensor on an epitaxial wafer having a structure including an epitaxial layer doped with a low dopant concentration positioned on a p-type or n-type substrate doped with a high concentration; forming a first photoresist layer over said structure, patterning the first photoresist layer, and etching the epitaxial layer so as to form a shallow trench on a pixel area defined by trench isolation structures; removing said first photoresist layer; forming a second photoresist pattern coexistive with said trench isolation structures so as to form a photodiode junction in at least a portion of the shallow trench of the pixel area, and, then, conducting ion-implanting process; and removing said second photoresist pattern and conducting a thermal treatment process.--.

Change claim 4 to --A method as defined by claim 1, wherein a final profile doped in said epitaxial layer doped with a low dopant concentration is formed on the top of a shallow trench isolation layer. --.

Allowable Subject Matter

4. Claims 1-6 are allowed over prior art of record.

Reasons for Allowance

5. The following is an examiner's statement of reasons for allowance:

The prior art of record neither anticipates nor renders obvious the claimed subject matter of the instant application as a whole either taken alone or in combination, in particular, prior art of record does not teach "etching the epitaxial layer so as to form a shallow trench on a pixel area defined by trench isolation structures; removing said first photoresist layer; forming a second photoresist pattern coexistive with said trench isolation structures so as to form a photodiode junction in at least a portion of the shallow trench of the pixel area, and, then, conducting ion-implanting process," as recited in claim 1.

Claims 2-6 are also allowed as being directly dependent of the allowed independent base claim.

Conclusion

6. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Correspondence

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Brook Kebede whose telephone number is (571) 272-1862. The examiner can normally be reached on 8-5 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (571) 272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Brook Kebede

Brook Kebede
Examiner
Art Unit 2823

BK
June 24, 2005